SCI AUTOMATION

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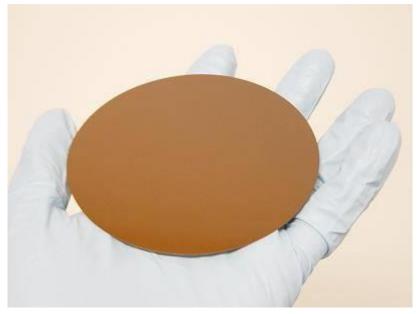




Dear Reader,

In this month's issue, we explore the capabilities of the **Juno**. As a standalone batch plasma system, Juno's chamber can accommodate a variable number of shelves, which provides you the flexibility of handling multiple hybrid substrates. With an alternating gas and vacuum supply in the chamber, thorough plasma homogeneity is assured.

Juno can be used for activation, cleaning and decontamination of semiconductor, automotive and medical products. It is ideal for surface activation and cleaning of polyimide flex substrates.



Polyimide substrate

WHY USE THE JUND

- Can be used for odd form substrates.
- Compact, standalone plasma cleaning system.
- Small footprint.
- Suitable for plasma etching.
- Suitable for Reactive Ion Etching.

SCI ANNOUNCEMENT

Please be informed that with effect from 12 March 2018,
Dr. Enrico Malatesta has stepped down from his role as
CEO of SCI Automation, and is now the Executive Chairman.

Please welcome our new CEO, Mr. Davide Zonca.

SCI Automation remains true to our mission to innovate and create high-tech plasma solutions.



Mr. Davide Zonca

SCI provides inline, strip and batch systems for lead frames, substrates, wafers, and modules.

View our products here!

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